

VLS GROWTH OF GaSe NANORIBBONS BY MOCVD



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CONTEXT

Gallium selenide (GaSe) is a layered semiconductor from the III-VI family which presents a tunable direct band gap of 2 eV. Optoelectronic properties of this material have already been demonstrated for photodetection applications [1-3]. Nevertheless, actual fabrication methods are based on exfoliated layers and there is a lack of large scale, good quality, elaboration method for 2D materials in general.

Working with one-dimensional objects could be an alternative to synthesize very good crystalline quality objects. Here, we demonstrate the VLS growth of GaSe nanoribbons (NRs) by MOCVD on 300 mm SiO2/Si substrates. The crystalline quality of these structures is investigated by HRTEM. Devices are realized on single NR, and optoelectronic properties are studied via photoluminescence and electrical characterizations.

III-VI FAMILY



- III-VI layered semiconductors family is post transition metals composed by monochalcogenide MXs (with M: Ga or In, X: S. Se or Te).
- Different direct band gap energy for each binary compounds.
- Possibility to combine them and tune the band gap by creating heterostructures.

Tetra-layer structure

X-M-M-X (X=Se, M=Ga)

GaSe PROPERTIES



Fig. 2 : Tetra-layer structure, Se-Ga-Ga-Se, side and top view

Fig. 3 : PL spectra of GaSe with different thickness ^[5]

Inter-layer spacing of 0,8 nm ^[6]

STRUCTURE

<u>1000 n</u>m d —PL at... (a.u.) Intensity 670 720 570 620 520 Wavelength (nm)

Fig. 5 : (a) STEM observation of dropcasted NRs on TEM membrane. (b) High magnification TEM image of the center of a nanoribbon. (c) High magnification

- **CRISTALLINE QUALITY**
 - GaSe nanoribbons : – Several nanometres wide (average width : 300 nm) Several micrometres long
 - Very good crystalline quality observed by HRTEM.
 - > No defect observed.
 - GaSe monolayers stacked along z-axis.
 - Very few nanotubes have been observed. Majority of structures grown are nanoribbons.
 - inter-layer > Measured spacing of 0.8 nm.
 - Energy gap measured by PL on several nanoribbons > Eg = 1.97 eV

OPTOELECTRONIC

- GaSe is generally p-type ^[7]
- E_a(GaSe) : 2,00 eV (bulk) ^[8]
- Direct band gap from some monolayers to multi-layers.
- Variation of band gap energy depending on the layer number
- Allow to cover a large spectral range.



200 nm

- MOCVD in Growth by industrial Applied Materials reactor on 300 mm SiO_2/Si .
- Indium droplets are used as catalysts initiate the to

TEM image of a NT. Inte-layer spacing measured to be 0.8 nm. (d) PL spectrum of several NRs



- Fig 6. Contacts are realised by e-beam lithography and Ni-Au are evaporated as electrodes materials. 6,3E-11
- Electrical measurements have been led under €^{1,9E-10} illumination (white light) and in dark, for temperatures ranging between 25 and 100°C.
- The current level increases with the temperature. Though, the current level is low. € 1,9E-10 F
 - > A photodetection behaviour is observed.
 - > Current level might be limited either by very



Fig. 4 : SEM images of as-grown NRs. In inset, a high magnification image shows the droplet sitting on top of a NR

growth.

- Observation of the catalyst at the end of the nanoribbons
- Consistent with Vapour-> Liquid-Solid (VLS) growth mechanism.

NRs doping level the bad or low Of contacts/GaSe interface.

CONCLUSION

Very good crystalline GaSe-NRs are synthesized via VLS mechanism in 300 mm MOCVD reactor. A photodetection behaviour is observed for a single NR.



Light OFF

50°C, 20V

75°C, 20V

6,3E-11

6,3E-11

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